10662892

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	19	semiconductor$2 and optical same tool and gas near flow and (absorptive or absorption or absorb$3) near (material or substance or layer or film) and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:23
S2	191	semiconductor$2 and optical same (toolor system) and gas near flow and (absorptive or absorption or absorb$3) near (material or substance or layer or film) and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 12:24
S3	195	semiconductor$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb$3) near (material or substance or layer or film) and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:19
S4	0	S3 and (optical near tool) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 12:34
S5	25	S3 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 12:45
S6	25	(US-20050117134-$ or US-20040166679-$ or US-20040086640-$ or US-20040023419-$ or US-20040006249-$ or US-20030113943-$ or US-20030068834-$ or US-20030021015-$ or US-20020142493-$ or US-20020126268-$ or US-20020044260-$ or US-20010038446-$).did. or (US-6884464-$ or US-6833949-$ or US-6759254-$ or US-6757051-$ or US-6621557-$ or US-6563578-$ or US-6538722-$ or US-6466365-$ or US-6411368-$ or US-5916712-$ or US-5738959-$ or US-5679483-$ or US-5302237-$).did.	US-PGPUB; USPAT	OR	ON	2005/06/17 12:45

S7	25	S6 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:19
S8	9	"6620630"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 21:59
S9	2	"5108178"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 00:30
S10	32	"5676760"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:45
S11	5	(US-20050117134-$ or US-20020126268-$).did. or (US-6757051-$ or US-6538722-$ or US-6411368-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 15:01
S12	16	"S8" and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 22:35
S13	5	S11 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:10
S14	2	(US-6757051-$ or US-6411368-$).did.	USPAT	OR	ON	2005/07/06 22:40
S15	2	S14 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:26

S16	1	S15 and saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:12
S17	0	S9 and saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:12
S18	24	(US-20050117134-$ or US-20040166679-$ or US-20040086640-$ or US-20040023419-$ or US-20040006249-$ or US-20030113943-$ or US-20030068834-$ or US-20030021015-$ or US-20020142493-$ or US-20020126268-$ or US-20020044260-$ or US-20010038446-$).did. or (US-6884464-$ or US-6833949-$ or US-6759254-$ or US-6757051-$ or US-6621557-$ or US-6563578-$ or US-6538722-$ or US-6466365-$ or US-6411368-$ or US-5916712-$ or US-5738959-$ or US-5679483-$ or US-5302237-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/06 23:12
S19	8	S18 and saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:14
S21	198	semiconductor$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb$3) near (material or substance or layer or film) and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:15
S22	46	S21 and saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:15

S23	6	S21 and (exceed$3 or pasted or past or passing or beyond) near2 saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:18
S24	6	semiconductor$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb$3) near (material or substance or layer or film) and photolithograph$4 and (exceed$3 or pasted or past or passing or beyond) near2 saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:19
S25	12	semiconductor$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb$3) near (material or substance or layer or film) and (exceed$3 or pasted or past or passing or beyond) near2 saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:29
S26	1	S15 and filter$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:27
S27	14	optical same (tool or system) and gas near flow and (absorptive or absorption or absorb$3) near3 (material or substance or layer or film) and (exceed$3 or pasted or past or passing or beyond) near2 saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:16
S28	172649	"438"/$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:35
S29	8	S28 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb$3) same (material or substance or layer or film) and (exceed$3 or pasted or past or passing or beyond) near2 saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 22:14

S30	10	S10 and saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:47
S31	0	S9 and saturat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 00:09
S32	1279	gas near flow and (absorptive or absorption) near3 (more or past)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:12
S33	202	S32 and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:08
S34	8	(US-20030113943-$ or US-20030068834-$ or US-20040166679-$ or US-20040023419-$).did. or (US-5567630-$ or US-6759254-$ or US-6620630-$ or US-5646050-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 10:16
S35	8	S34 and saturation	US-PGPUB; USPAT	OR	ON	2005/07/07 10:16
S36	2	(US-6757051-$ or US-6411368-$). did.	USPAT	OR	ON	2005/07/07 12:12
S37	2	S36 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 17:21
S38	0	S37 and gas near flow and (absorptive or absorption) near3 (more or past)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:12

S39	2	S37 and gas near flow and (absorptive or absorption)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:12
S40	1738	optical same (tool or system) and gas near flow and (absorptive or absorption or absorb$3) near3 (material or substance or layer or film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:18
S41	110	S40 and (gas near flow) same ((absorptive or absorption or absorb$3) near3 (material or substance or layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:19
S42	50	S40 and (gas near flow) same ((absorptive or absorption or absorb$3) near3 material)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:36
S43	308	S40 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:30
S44	16	S42 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 16:52
S45	10	S42 and ((absorptive or absorption or absorb$3) near3 material) same glass	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:22
S46	3	(US-20010028992-$).did. or (US-4913260-$ or US-6629375-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 12:30

S47	24	(US-20050117134-$ or US-20040166679-$ or US-20040086640-$ or US-20040023419-$ or US-20040006249-$ or US-20030113943-$ or US-20030068834-$ or US-20030021015-$ or US-20020142493-$ or US-20020126268-$ or US-20020044260-$ or US-20010038446-$).did. or (US-6884464-$ or US-6833949-$ or US-6759254-$ or US-6757051-$ or US-6621557-$ or US-6563578-$ or US-6538722-$ or US-6466365-$ or US-6411368-$ or US-5916712-$ or US-5738959-$ or US-5679483-$ or US-5302237-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 12:38
S48	24	S47 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:21
S49	0	S48 and photolighograph$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:25
S50	24	S48 and photolithograph$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:39
S51	8759	"I7" and (absorptive or absorption or absorb$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:20
S52	24	S48 and (absorptive or absorption or absorb$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:20

S53	15	optical same tool and gas near flow and (absorptive or absorption or absorb$3) near material and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:17
S54	132065	"250"/$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:27
S55	175	S54 and gas near flow and (absorptive or absorption or absorb$3) near material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:03
S56	20	S54 and gas near flow same (absorptive or absorption or absorb$3) near material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:07
S57	0	"230"/$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:07
S58	91611	"356"/$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:17
S59	2	S58 and optical same tool and gas near flow and (absorptive or absorption or absorb$3) near material and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:19
S60	5	S58 and optical same tool and gas near flow and (absorptive or absorption or absorb$3) near material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:19

S61	0	S41 and photolighograph$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:25
S62	24	S41 and photolithograph$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:25
S63	11	S47 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:16
S64	3	(US-6757051-$ or US-6538722-$ or US-6411368-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 15:01
S65	4	(US-5108178-$ or US-5686996-$ or US-6411368-$ or US-6757051-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 15:02
S66	5	(US-5108178-$ or US-5686996-$ or US-6411368-$ or US-6757051-$ or US-5676760-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 16:30
S67	1	S66 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:10
S68	31	S55 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:29
S69	195	((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:57
S70	22	((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow same (bead$2 or sphere$2 or blob$2 or bubble$2 or ball$2 or orb$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 23:32

S71	16	((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow same (bead$2 or sphere$2 or blob$2 or ball$2 or orb$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 16:17
S72	5	(US-6491885-$ or US-4002722-$). did. or (US-3486298-$ or US-3339350-$ or US-3263400-$). did.	USPAT; USOCR	OR	ON	2005/07/07 16:26
S73	7	(US-5108178-$ or US-5686996-$ or US-6411368-$ or US-6757051-$ or US-5676760-$ or US-4002722-$ or US-6491885-$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 22:30
S74	2	S73 and gas near flow and optical near (system or tool)	US-PGPUB; USPAT	OR	ON	2005/07/07 16:39
S75	2	S74 and (absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 16:39
S76	2	S73 and (gas near flow) same (optical near (system or tool))	US-PGPUB; USPAT	OR	ON	2005/07/07 16:43
S77	2	S76 and (absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 17:19
S78	2	S77 and gas near flow	US-PGPUB; USPAT	OR	ON	2005/07/07 16:43
S79	6	S73 and gas near flow	US-PGPUB; USPAT	OR	ON	2005/07/07 17:05
S80	2	S75 and (absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 17:19
S81	63	(optical same(tool or system)) same (gas near flow) and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:38
S82	7	S73 and gas$3	US-PGPUB; USPAT	OR	ON	2005/07/07 17:39
S83	4	S73 and gas$3 same (filter$3 or purg$4)	US-PGPUB; USPAT	OR	ON	2005/07/07 17:48
S84	5	S73 and gas$3 same (filter$3 or purg$4 or absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 18:04
S85	2	S84 and (tubular or tub$3)	US-PGPUB; USPAT	OR	ON	2005/07/07 18:57
S86	1	S85 and (reflect$4 or refract$4 or deflect$4)	US-PGPUB; USPAT	OR	ON	2005/07/07 18:26

S87	12	S81 and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:41
S88	10	S87 and contaminat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:42
S89	5	S73 and contaminat$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 19:05
S90	3	S73 and contaminat$4 and photolithograph$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:43
S91	1	S85 and optical$4	US-PGPUB; USPAT	OR	ON	2005/07/07 18:57
S92	4	S89 and (light$2 or optical$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 22:15
S93	4	(US-6757051-$ or US-6411368-$ or US-5686996-$ or US-5108178-$).did.	USPAT	OR	ON	2005/07/08 00:23
S94	2	S93 and vacuum$2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 22:15
S95	642128	S93 regula$4	USPAT	OR	ON	2005/07/07 22:16
S96	3	S93 and regula$4	USPAT	OR	ON	2005/07/07 22:29
S97	2	S93 and polymer$3	USPAT	OR	ON	2005/07/07 23:01
S99	3	S93 and (oxygen or water)	USPAT	OR	ON	2005/07/07 23:04
S100	3	S93 and (oxygen or water or liquid$2)	USPAT	OR	ON	2005/07/07 23:04
S101	2	(US-4002722-$ or US-6491885-$).did.	USPAT	OR	ON	2005/07/07 23:31

S10 2		2	S101 and glass	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 23:31
S10 3		2	S102 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow same (bead$2 or sphere$2 or blob$2 or bubble$2 or ball$2 or orb$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:19
S10 4		0	S103 and (semiconductor$2 or wafer$2 or photolithograph$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:20
S10 5		3	S93 and (semiconductor$2 or wafer$2 or photolithograph$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:23
S10 6		5	(US-6757051-$ or US-6411368-$ or US-5686996-$ or US-5108178-$ or US-5676760-$).did.	USPAT	OR	ON	2005/07/08 00:23
S10 7		4	S106 and (semiconductor$2 or wafer$2 or photolithograph$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:25
S10 8		1	S107 and atomic near absorption	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:27
S10 9		1	S107 and atomic near absorption and gas$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:35
S11 0		1	S107 and atomic near absorption and gas$3 and photolithograph$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:36

S11 1	1	(US-5676760-$).did.	USPAT	OR	ON	2005/07/08 00:36
S11 2	1	S111 and atomic near absorption and gas$3 and photolithograph$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:54
S11 3	16294	438/7,14,16,102,115,101,166,22, 365,482,487,509,513,540,57,597, 603,618,635,680,783,784,795. ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:55
S11 4	0	S113 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor$2 or wafer$2 or photolithograph$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:02
S11 5	7278	250/305,338,339,306,440.11,441. 11,442.11,443,345,373,504,336.1, 338.5,339.04,370.01,374.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:02
S11 6	0	S115 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor$2 or wafer$2 or photolithograph$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:03
S11 7	9801	257/66,629,687,700,713,78-80, 99.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:03
S11 8	0	S117 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor$2 or wafer$2 or photolithograph$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:04

S11 9	4201	356/246,432,437,499.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:04
S12 0	0	S119 and ((absorptive or absorption or absorb$3) near3 material) same (glass or polymer$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor$2 or wafer$2 or photolithograph$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:04